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JFW

PATENT

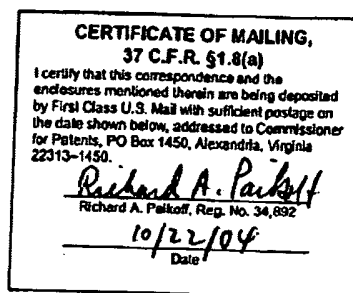
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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application No. : 10/040,042 Confirmation No. 1835
Applicant : Wei-Yu Su
Filed : November 7, 2001
TCA.U. : 1746
Title : Method for Reduction of Photomask Defects

Docket No. : N1085-90003
Customer No. : 08933

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

OK TO
ENTER
12/7/04
C. J. JueAMENDMENT AND RESPONSE UNDER 37 CFR §116(a)Do not enter
ZE 11/8/04

Sir:

In response to the Office Action of August 27, 2004, please amend the above-identified application as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks begin on page 5 of this paper.